

~~D apparatus a  
d in said cham  
D apparatus a  
d in said cham~~

--20. The CVD apparatus according to claim 18, wherein an electrode for plasma generation is disposed in said chamber.

generation is disposed in said chamber.

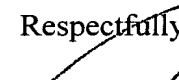
# THE FUTURE OF THE FUTURE

Care has been taken so as to avoid the addition of new matter in the specification, claims and abstract.

Entry of the present Preliminary Amendment prior to the examination of the application is respectfully requested.

# THE UNIVERSITY OF CHICAGO

Respectfully submitted,



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